

AMENDMENT TRANSMITTAL LETTER

Docket No.
M4065.0353/P353-A

Application No.
09/982,954

Filing Date
October 22, 2001

Examiner
Karla Moore

Art Unit
1763

Applicant(s): Gurtej Sandhu, et al.

Invention: ATOMIC LAYER DOPING APPARATUS AND METHOD

TO THE COMMISSIONER FOR PATENTS

Transmitted herewith is an amendment in the above-identified application.

The fee has been calculated and is transmitted as shown below.

CLAIMS AS AMENDED					
	Claims Remaining After Amendment	Highest Number Previously Paid	Number Extra Claims Present	Rate	
Total Claims	19	- 20 =		x	0.00
Independent Claims	3	- 3 =		x	0.00
Multiple Dependent Claims (check if applicable) <input type="checkbox"/>					
Other fee (please specify):					
TOTAL ADDITIONAL FEE FOR THIS AMENDMENT:					0.00

☒ Large Entity

☐ Small Entity

☒ No additional fee is required for this amendment.

☐ Please charge Deposit Account No. _____ in the amount of \$ _____.
A duplicate copy of this sheet is enclosed.

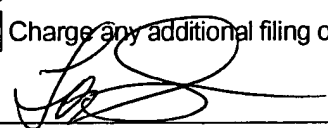
☐ A check in the amount of \$ _____ to cover the filing fee is enclosed.

☐ Payment by credit card. Form PTO-2038 is attached.

☒ The Commissioner is hereby authorized to charge and credit Deposit Account No. 04-1073
as described below. A duplicate copy of this sheet is enclosed.

☒ Credit any overpayment.

☒ Charge any additional filing or application processing fees required under 37 CFR 1.16 and 1.17.


Thomas J. D'Amico
Attorney Reg. No.: 28,371

Dated: December 26, 2002

DICKSTEIN SHAPIRO MORIN & OSHINSKY LLP
2101 L Street NW
Washington, DC 20037-1526
(202) 828-2232

RECEIVED
DEC 27 2002
TC 1700



Docket No.: M4065.0353/P353-A
(PATENT)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:
Gurtej Sandhu et al.,

Application No.: 09/982,954

Group Art Unit: 1763

Filed: October 22, 2001

Examiner: Karla Moore

For: ATOMIC LAYER DOPING APPARATUS
AND METHOD

#13
12/31/02
ML

AMENDMENT

Commissioner for Patents
Washington, DC 20231

Dear Sir:

Responsive to the Office Action of September 26, 2002, rejecting claims 1-17,
please amend the above-identified U.S. patent application as follows:

In the Claims:

Please add new claims 46 and 47.

RECEIVED
DEC 27 2002
TC 1700

46. (new) An atomic layer doping apparatus comprising:

B₁ a first atomic layer doping region for depositing a first dopant species on a
first substrate as a monolayer;

a second atomic layer doping region for diffusing said first dopant species in
said first substrate, said first and second doping regions being chemically isolated from one
another by an inert gas curtain, wherein said inert gas curtain is provided at a higher
pressure than said first dopant species; and,